



QS1200™

FTIR Metrology For Wafer Processing

Nanometrics presents the QS-1200 desktop system for dopant monitoring, epi thickness measurement, and other applications. The QS-1200 is designed for advanced semiconductor fabs performing material characterization in silicon growing and device manufacturing areas. It provides a new level of integration of the FTIR technique utilizing proven optical technology, and a manual wafer tray to accommodate SEMI standard wafer sizes of 100, 125, 150, 200, and 300 mm. Odd shaped wafer pieces, and 2 mm thick silicon slices can also be used on the QS-1200. An available option is a single wafer mapping (r, theta) stage for all the above wafer sizes.

Typical Applications

- Epitaxial film thickness
- Film thickness (dielectric, wafer, MEMs)
- Interstitial oxygen and substitutional carbon in silicon
- Boron and phosphorus in BPSG
- Hydrogen in SiN and SiON passivation layer
- Fluorine in FSG layers
- General purpose FTIR analysis
- Contact Nanometrics for detailed list of applications



QS-1200

Nanometrics Incorporated
1550 Buckeye Drive
Milpitas, CA 95035
tel: 408.435.9600
fax: 408.232.5910
sales@nanometrics.com
www.nanometrics.com

nanometrics
Predictive Metrics for the Nano World

System Description

- Non-contact and non-destructive FTIR technique for a large number of applications using Nanometrics' proven FTIR technology and proprietary algorithms
- High sensitivity ensured by large optical aperture, self-aligning interferometer and related optics
- QS-1200 PC system is fully GEM compliant and the SECS interface supports local and remote control operation by the host via HSMS/SECS-1 protocols
- Transmission and reflection measurements
- Unlimited measurement pattern and 2D/3D mapping
- Faster installation and qualification
- Easy recipe transfer

Easy to Use

In its basic configuration, the instrument consists of an FTIR-based optical console and a manual wafer tray to accommodate SEMI standard wafers ranging in diameter from 100 to 300 mm, or odd shaped silicon slices. The instrument is controlled by a powerful PC with Microsoft® Windows XP operating system. With the optional single wafer mapping stage, unlimited wafer mapping measurements can be made.

The easy-to-use Nanometrics WIN application software contains routines to create patterns to map and recipes to process the wafers. The measurement results are stored in a Microsoft Access™ database with easy export to other database formats such as Excel™. When the optional mapping stage is used, the measurement results also can be used to generate contour maps to determine the uniformity.

Specifications

System Performance

Uptime	> 98%
MTBF	> 2,000 hours
MTBA	> 1,000 hours
MTTR	< 4 hours

